

AMENDMENTS TO THE SPECIFICATION:

1. Please amend the paragraph beginning on page 18, line 17, as follows:

All the characters each [[have]] has a size that allows irradiating by one shot of the electron beam. Character apertures corresponding to the individual characters are arranged over the second shaping aperture mask, as shown in FIG. 6. That is, using the characters of 26 types, the character patterns in the sub deflection region 502 can be exposed by 73 shots in total.

2. Please amend the paragraph beginning on page 22, line 16, and ending on p. 23, line 1, as follows:

To this end, a description will now be made hereunder regarding a sorting condition (E) by way of one aspect of a method of first embodiment of the invention. In setting the sorting condition (E), restrictions for character switching are eliminated. Concurrently, the condition (E) is set such that a shot sequence is determined so as to reduce the total settling time of the two deflectors to be minimum in consideration of the characteristics of the settling times of the two deflectors, namely, the sub deflector 413 and the shaping deflector 409. More specifically, each settling time ~~is determined~~ is determined in the following conditions: